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PROCESS CONTROL THEORY AND THE CPI...

IS THERE A BRIGHTER FUTURE SHINING THROUGH ALL THAT JARGON?

Despite its advances, process control theory has been slow to realize its full potential in the chemical processing industry. Control experts have "theorized" themselves out of the industrial loop. Control remains mostly an afterthought to process design. Yet safety and economics clearly demand more high-performance, non-linear control techniques in the CPI. Those are among the important issues addressed in the new volume of Chemical Process Control—CPCIV. This 700-page compendium contains 37 of the most significant papers from the Fourth International Conference on Chemical Process Control. It covers virtually every topic in the field that chemical engineers should know about. From inventory control in Japanese plants to modeling in neurobiology, these papers sum up five years of the very latest control applications from industry, academia, and government.

CHEMICAL PROCESS CONTROL—
CPCIV, 1991, edited by Yaman Arkun, Georgia Institute of Technology, and W. Harmon Ray, University of Wisconsin.

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